

# Monte Carlo Solution to Excess Noise and Spatial Blur in Amorphous Selenium Thin-films

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Amorphous selenium (*a*-Se) is emerging as a viable solid-state imager with avalanche gain for low-light and low-dose radiation detection applications. [1] At high electric fields, hole transport in *a*-Se can be shifted entirely from localized to extended states, resulting in deterministic and non-Markovian impact ionization avalanche (excess noise factor,  $ENF \sim 1$ ) ~Fig. 1. To understand this behavior, a comprehensive study of the history dependent and non-Markovian nature of the hot hole transport in *a*-Se was performed using a Monte Carlo (MC) random walk of single hole free flights, interrupted by instantaneous phonon, disorder, hole-dipole, and impact-ionization scattering processes.

Our multi-scale simulation approach combines molecular dynamics (MD) simulations with density functional theory (DFT) and MC simulations (using a non-parabolic band model). The energy and phonon band structure ~Fig. 2, along with the valence band density of states (VB-DOS), for trigonal selenium (*t*-Se), was calculated using density functional theory (DFT). Fig. 3 shows the DFT calculated acoustic (first order) and optical (zeroth order) deformation potentials along the perpendicular and parallel directions to the *c*-axis in *t*-Se. According to our knowledge, this work for the first time uses comprehensive quantum mechanical formulation to calculate energy depended phonon scattering (acoustic, polar emission/absorption and non-polar emission/absorption), hole-dipole disorder scattering (caused by valence alternate pair type defects as scattering centers), and impact ionization scattering rates in *a*-Se.[2], [3]

Fig. 4 shows the simulated  $ENF$  in 0.1-15  $\mu\text{m}$  *a*-Se thin-films. The non-Markovian nature of hot hole branching dominates for thinner thin films where

the dead space distance (min distance traveled to attain impact ionization) is a multiple of the device length. In ~Fig. 5 (a) and (b) we simulated the threshold distance and gain distributions. The history dependent nature of branching of *Hot* holes is explained using a Gaussian distribution of the avalanche threshold distribution distance which increases determinism in the stochastic impact ionization process. An almost ideal non-Markovian hole  $ENF$  of  $\sim 1$  was observed in the case of 100 nm *a*-Se thin-films and avalanche gains of 1000. An inherent limitation to spatial resolution is the lateral blur caused due to the hole drifting process in *a*-Se, and, we calculate and predict the spatial blur and the full width at half max (FWHM) spread of the avalanching charge cloud in 0.5-200  $\mu\text{m}$  *a*-Se films ~Fig. 6. Future detector designs can utilize the non-local/non-Markovian nature of hole avalanche in *a*-Se, to enable a true solid-state photomultiplier with noiseless gain and enhanced signal to noise ratios.

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## REFERENCES

- [1] A. Mukherjee, D. Vasileska, A. H. Goldan, *et al.*, "Vertical architecture solution-processed quantum dot photodetectors with amorphous selenium hole transport layer," *ACS Photonics*, vol. 10, no. 1, pp. 134–146, 2023.
- [2] A. Mukherjee, D. Vasileska, J. Akis, and A. H. Goldan, "Monte carlo solution of high electric field hole transport processes in avalanche amorphous selenium," *ACS omega*, vol. 6, no. 7, pp. 4574–4581, 2021.
- [3] A. Mukherjee, D. Vasileska, and A. Goldan, "Hole transport in selenium semiconductors using density functional theory and bulk monte carlo," *J. Appl. Phys.*, vol. 124, no. 23, p. 235102, 2018.

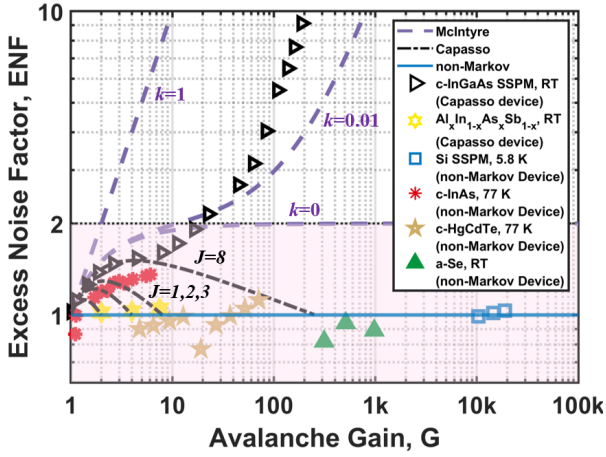


Fig. 1. Excess noise factor in *a*-Se compared with Markov, non-Markov and Capasso type devices.

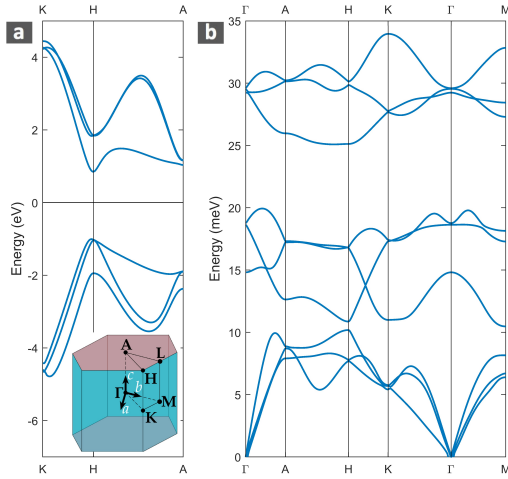


Fig. 2. (a) DFT calculated electronic bandstructure for *t*-Se showing a direct bandgap of 1.9 eV at the H point and (b) phonon dispersion. Inset shows the Brillouin zone for *t*-Se.

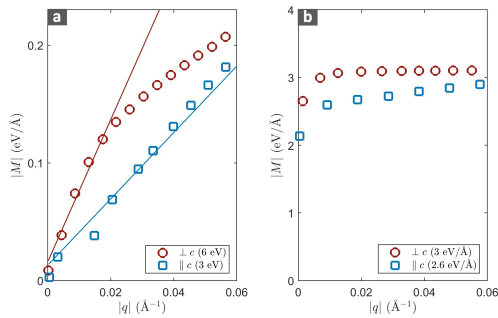


Fig. 3. (a) Acoustic (first order) deformation potentials represented by the slope of solid lines and (b) optical (zeroth order) deformation potential measured via DFT calculations of hole-phonon coupling using a 225-atom supercell of *t*-Se along directions perpendicular and parallel to the *c*-axis.

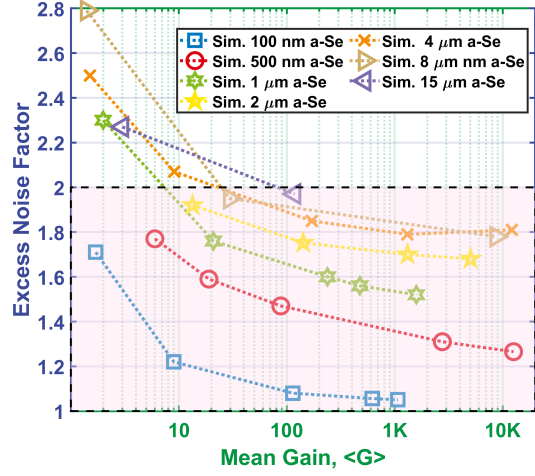


Fig. 4. Plot of *ENF* from single hole MC simulations for 0.1-15  $\mu\text{m}$  *a*-Se bulk drift length as a function of mean gain.

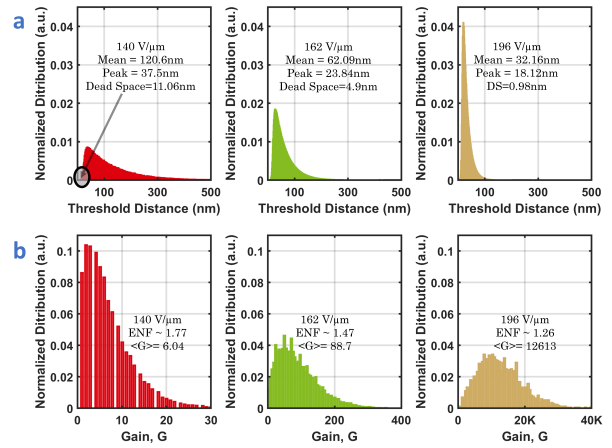


Fig. 5. (a) Threshold distance distributions and (b) avalanche gain distribution for 500 nm *a*-Se bulk drift lengths for electric field strengths of 140, 162 and 196  $\text{V}/\mu\text{m}$ , respectively.

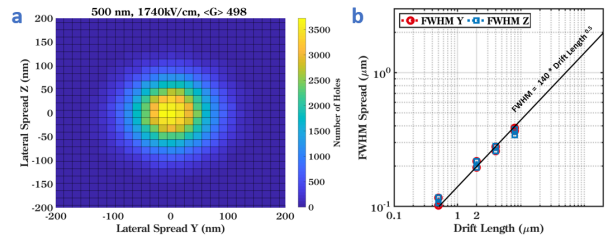


Fig. 6. (a) Increase in the spatial spread of a charge cloud of 500 holes injected at  $x = 0$ . The lateral spread as a function of electric field at the end of 500 nm of travel in *a*-Se is simulated for 174  $\text{V}/\mu\text{m}$ . (b) The FWHM simulated for *a*-Se drift lengths of 500 nm, 2  $\mu\text{m}$ , 4  $\mu\text{m}$  and 8  $\mu\text{m}$ .